

Mitigating Parameter Variation with Dynamic Fine-Grain Body Biasing*

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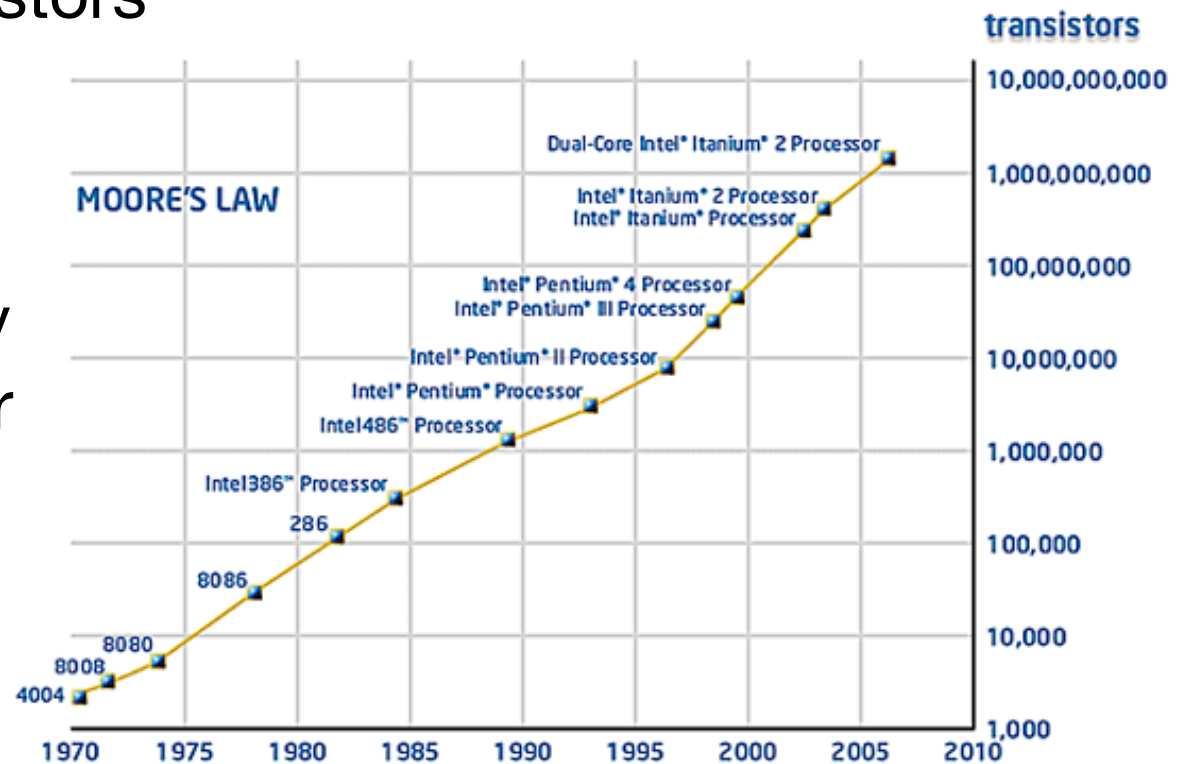
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Motivation

- Technology scaling continues
- More and more transistors every generation!
- However...
- Chips are increasingly affected by parameter variation

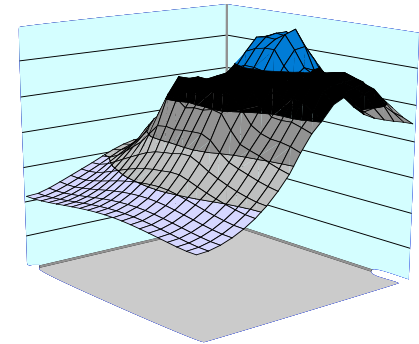
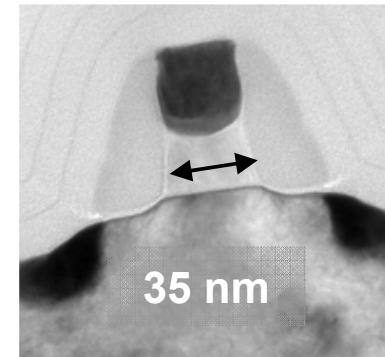


Intel Corp.



Parameter Variation

- Process variation
 - Manufacturing at low feature sizes
- Temperature variation
 - Uneven activity distribution
- Supply voltage variation
 - IR drop, di/dt noise



Intel Corp.

Effects of Parameter Variation

- Higher power consumption
- Lower frequency
- Uncertainty in the design process



Outline

- A Model of Process Variation
- Dynamic Fine-Grain Body Biasing
- Evaluation
- Conclusions



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A Model For Process Variation

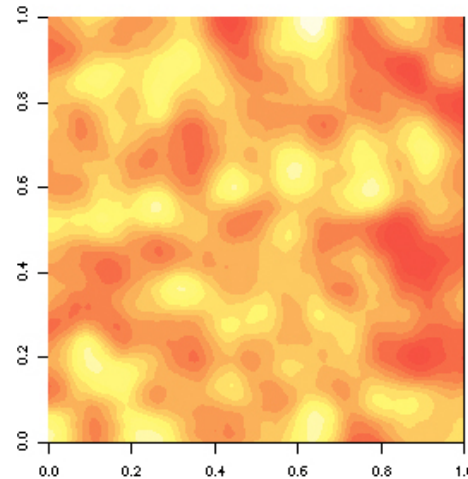
- Fast, simple and parameterizable model
- We model two key process parameters:
 - Transistor critical dimension (L_{eff}) and threshold voltage (V_{th})
- We also model temperature effects



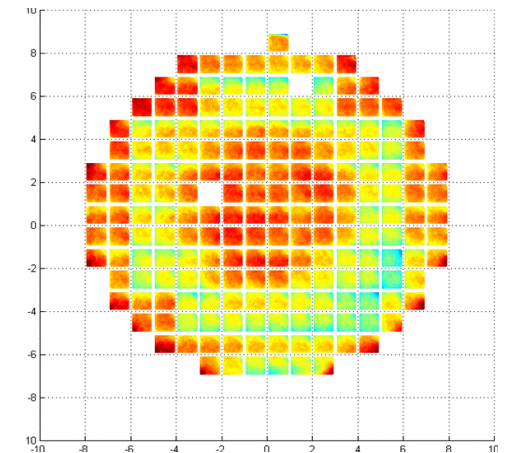
Variation Components

- Granularity:
 - Within die
 - Die-to-die

Within die



Die-to-die



- WID variation:
 - Systematic variation
 - Random variation

A Model For Process Variation

- Variation in any parameter P:

$$\Delta P = \Delta P_{D2D} + \Delta P_{WID} = \Delta P_{D2D} + \Delta P_{rand} + \Delta P_{sys}$$

- We focus on WID variation
 - D2D is a chip-wide offset to ΔP_{WID}
- Random and systematic components
 - Modeled as normal distributions
 - Treated separately - impact different levels of the microarchitecture

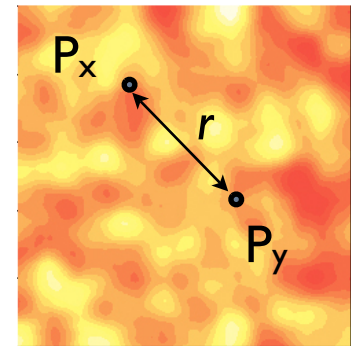


Systematic Variation

- We divide the chip into a grid of points
 - Each point has one random value of ΔP_{sys}
- Multivariate normal distribution ($\mu_{\text{sys}}=0, \sigma_{\text{sys}}$)

- Characterized by a correlation function:

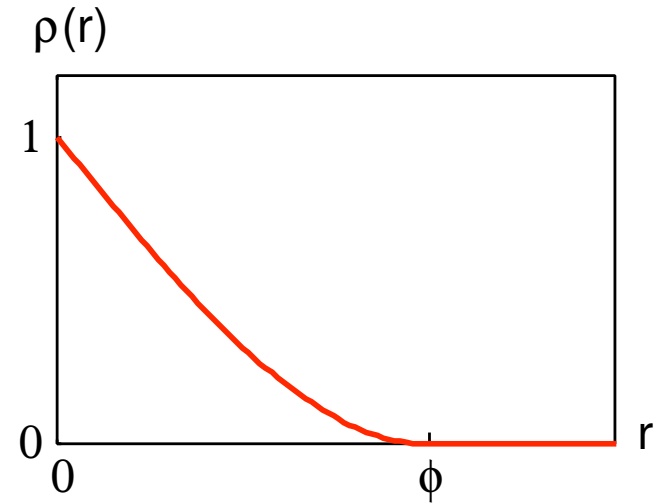
$$\text{corr}(P_{\vec{x}}, P_{\vec{y}}) = \rho(r) ; r = |\vec{x} - \vec{y}|$$



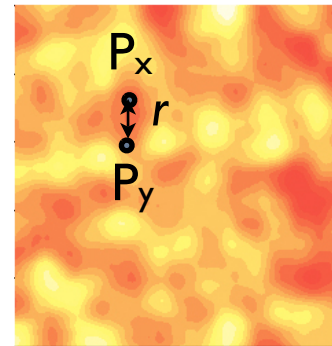
- Correlation is position independent and isotropic
- For $\rho(r)$ we choose the spherical model

Spherical Model

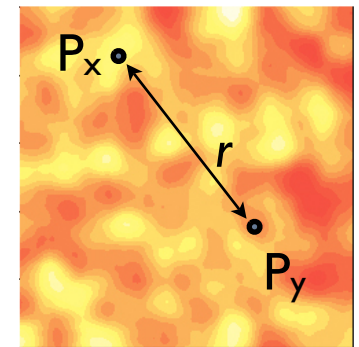
$$\rho(r) = \begin{cases} 1 - \frac{3r}{2\phi} + \frac{r^3}{2\phi^3} & : (r \leq \phi) \\ 0 & : \text{otherwise} \end{cases}$$



Stronger correlation



Weaker correlation



- Matches measured data [Friedberg et al. 05]

Random Variation

- Random variation - transistor level
- We model it analytically as a normal distribution
- Both ΔP_{rand} and ΔP_{sys} are normal and independent with σ_{rand} and σ_{sys}

$$\sigma_{total} = \sqrt{\sigma_{rand}^2 + \sigma_{sys}^2}$$



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Body Biasing

- Well known technique for V_{th} control
- A voltage is applied between source/drain and substrate of a transistor
- Forward body bias

FBB - V_{th} ↓ - Freq ↑ - Leak ↑

- Reverse body bias

RBB - V_{th} ↑ - Freq ↓ - Leak ↓

- Useful knob to control frequency and leakage



Body Bias Design Space

Time / Space	Static	Simple adaptation	Dynamic
	BB fixed for chip lifetime	FBB in active mode RBB in standby	BB changes with T and workload
Chip-wide	<ul style="list-style-type: none"> D2D variation [Intel Xscale]	<ul style="list-style-type: none"> D2D variation, power, performance [Intel's 80-core chip]	
Fine-grain	<ul style="list-style-type: none"> WID variation [Tschanz et al]	<ul style="list-style-type: none"> WID variation, power, performance 	<ul style="list-style-type: none"> WID variation T variation (space and time)



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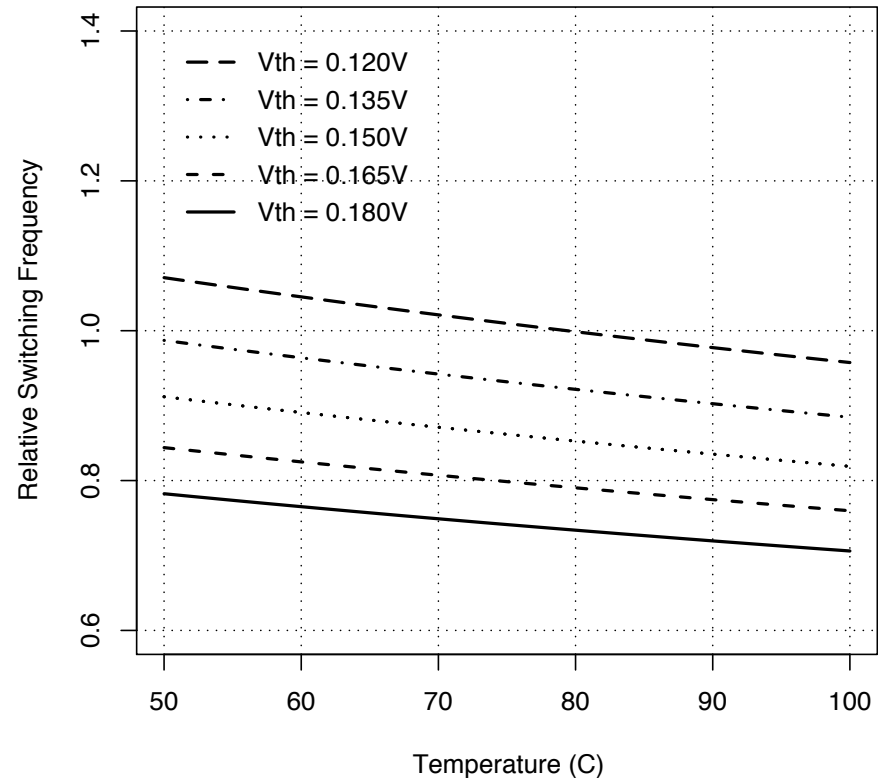
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Motivation for D-FGBB

- Body bias trades off frequency for leakage
- **Optimal** body bias:
The **lowest** FBB or **highest** RBB s.t. circuit delay meets frequency target



- Circuit delay changes with temperature
- Therefore optimal BB changes with temperature

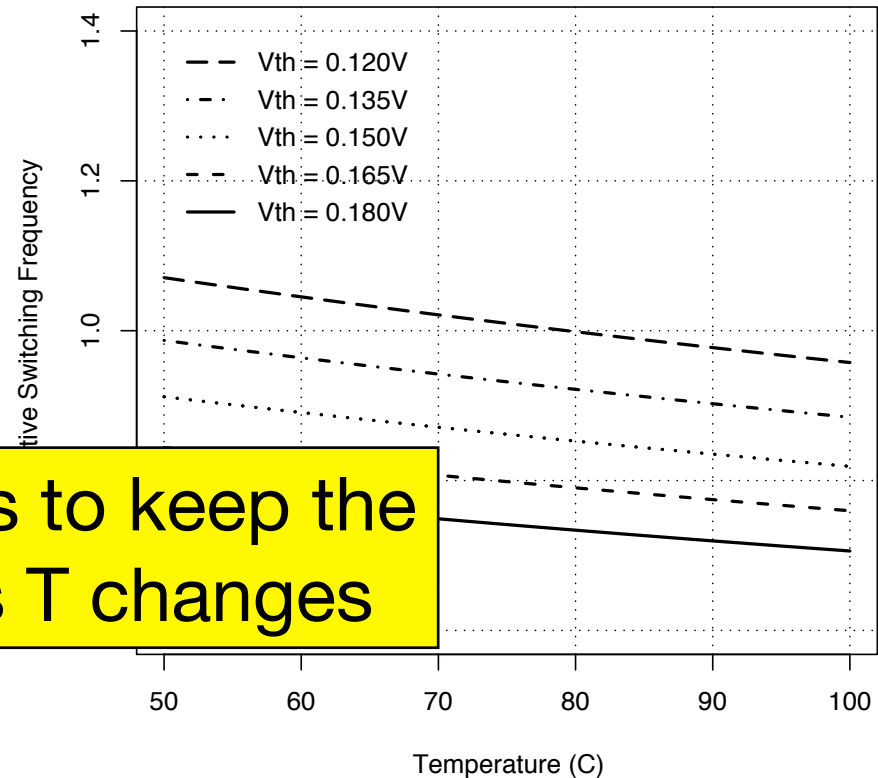


Motivation for D-FGABB

- Body bias trades off frequency for leakage
- **Optimal** body bias:

The **lowest** FRB or **highest** BRB
s.t. circuit delay < target

The goal of D-FGABB is to keep the body bias optimal as T changes

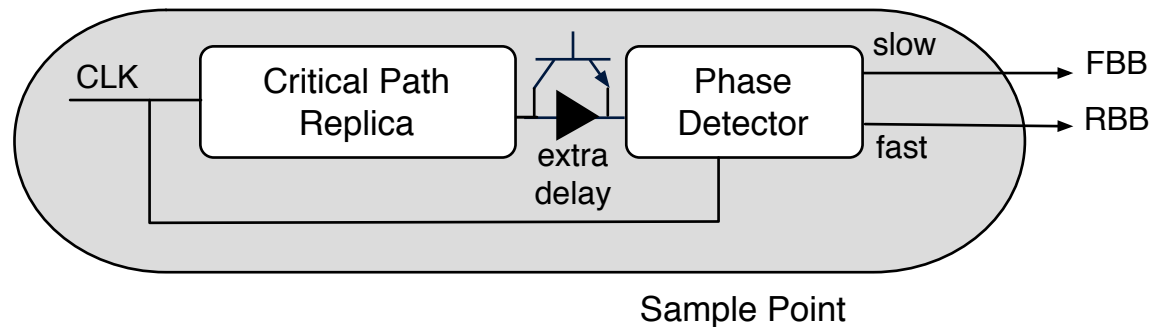


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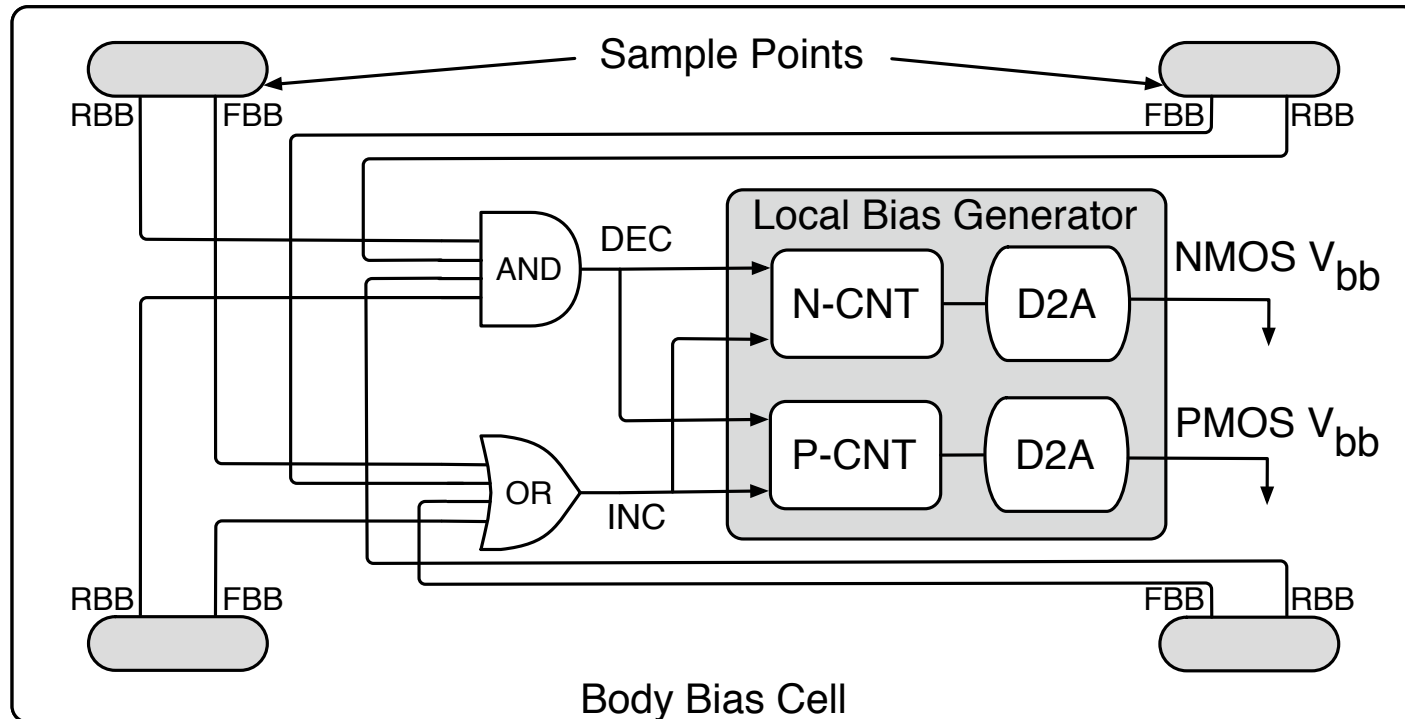


Finding the Optimal BB

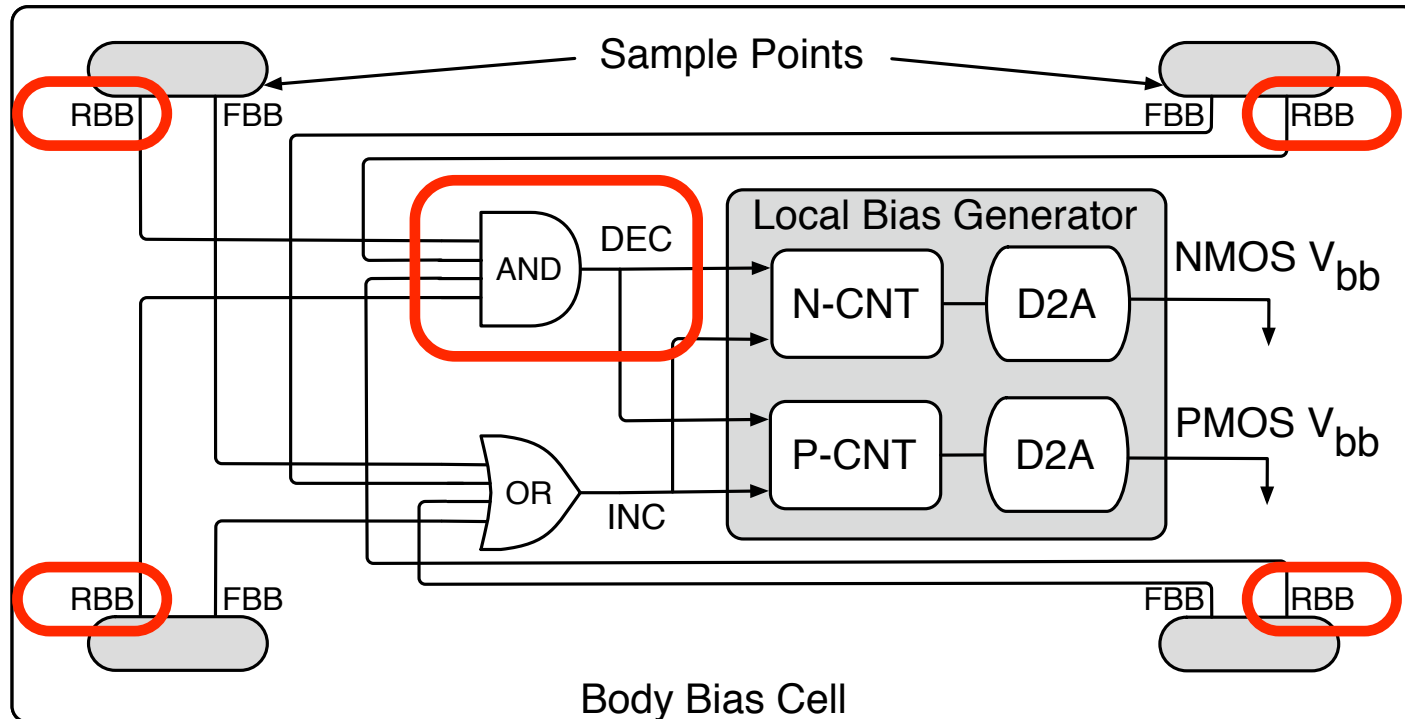
- Measure the delay of each BB cell
- Critical path replicas to sample cell delay
- Phase detector “times” the critical path replica
- If slow - FBB signal raised
- If fast - RBB signal raised



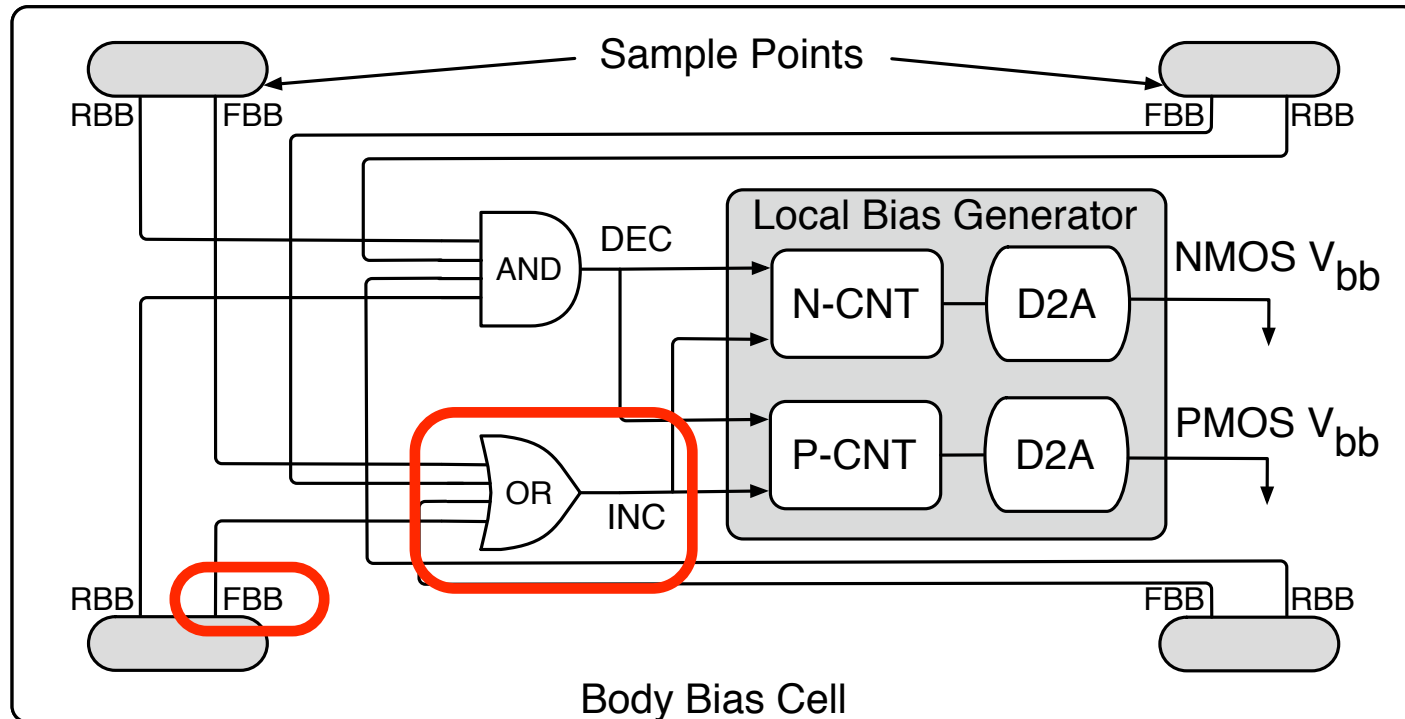
Applying Fine Grain BB



Applying Fine Grain BB



Applying Fine Grain BB



Applications of D-FGGB

Operating environments	S-FGGB	D-FGGB
Normal	Improve chip operating point	Save leakage power
High Performance	Improve chip operating point	Increase average frequency
Low Power	Save leakage power	Save leakage power

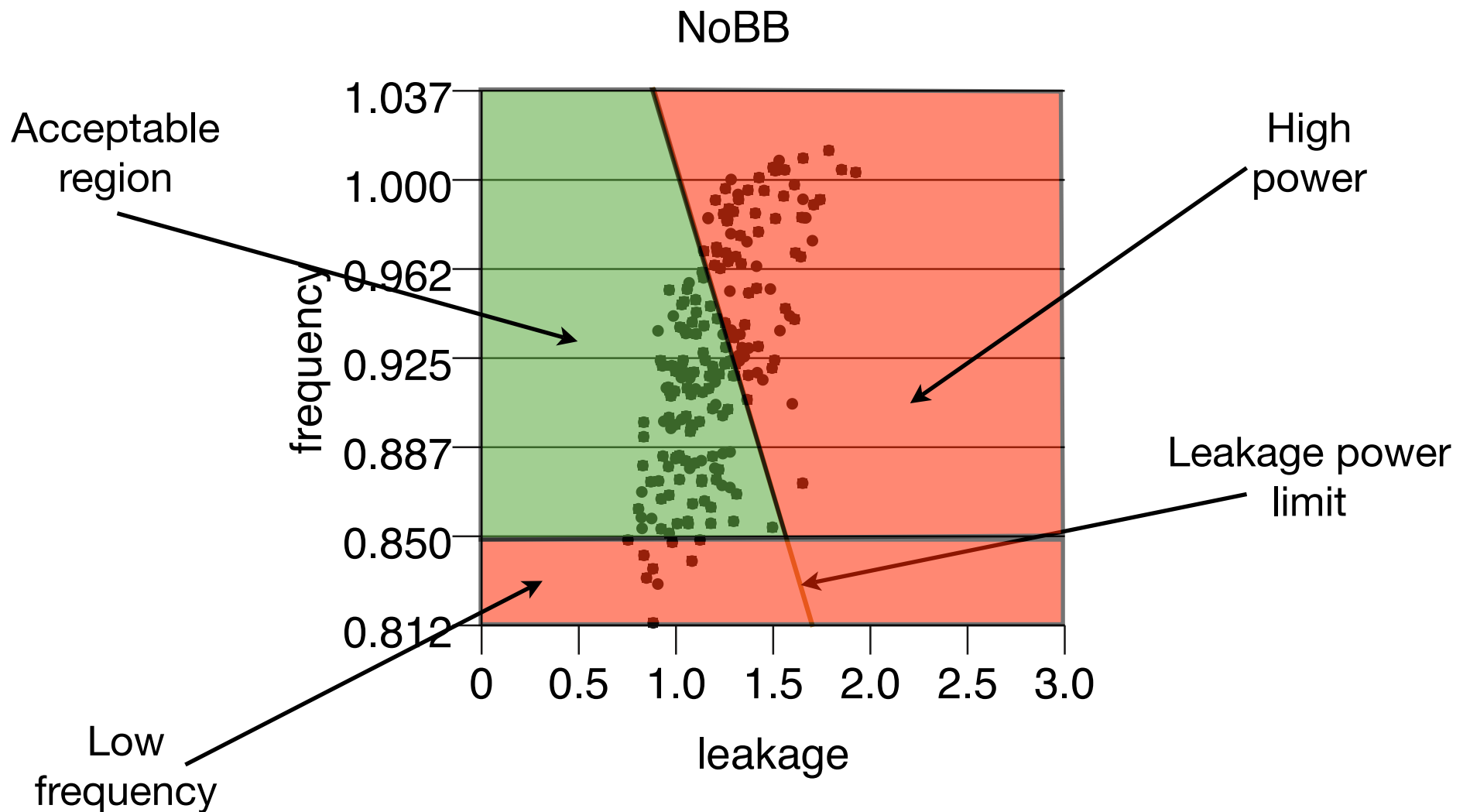


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Improving a Chip's Operating Point



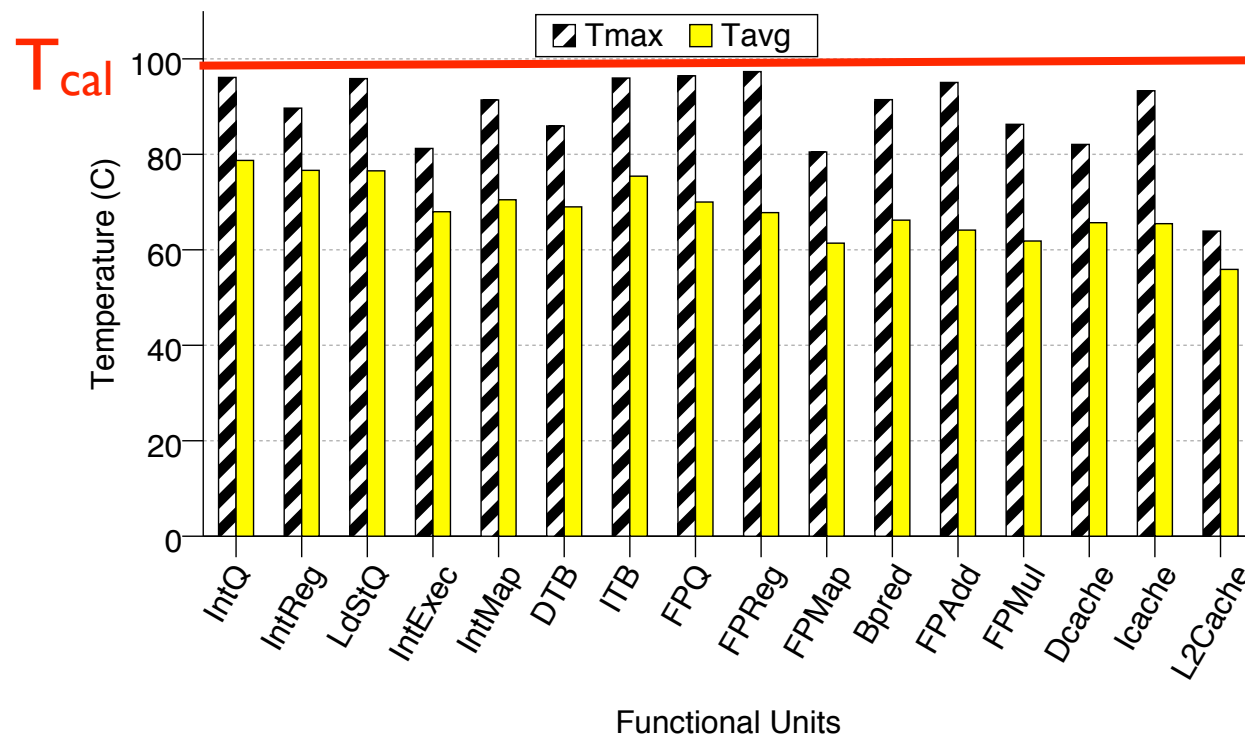
Improving a Chip's Operating Point

- Post-manufacturing calibration phase:
 1. Bring chip to T_{cal}
 2. Set target frequency F_{cal}^0 , and run at full load
 3. BB is adjusted automatically
 4. Measure total power P_{cal} : if $P_{cal} < P_{target}$,
 $F_{cal}^1 = F_{cal}^0 ++$, else $F_{cal}^1 = F_{cal}^0 --$
 5. Repeat if needed, until $P_{cal} \approx P_{target}$
- F_{cal}^i becomes the chip's frequency



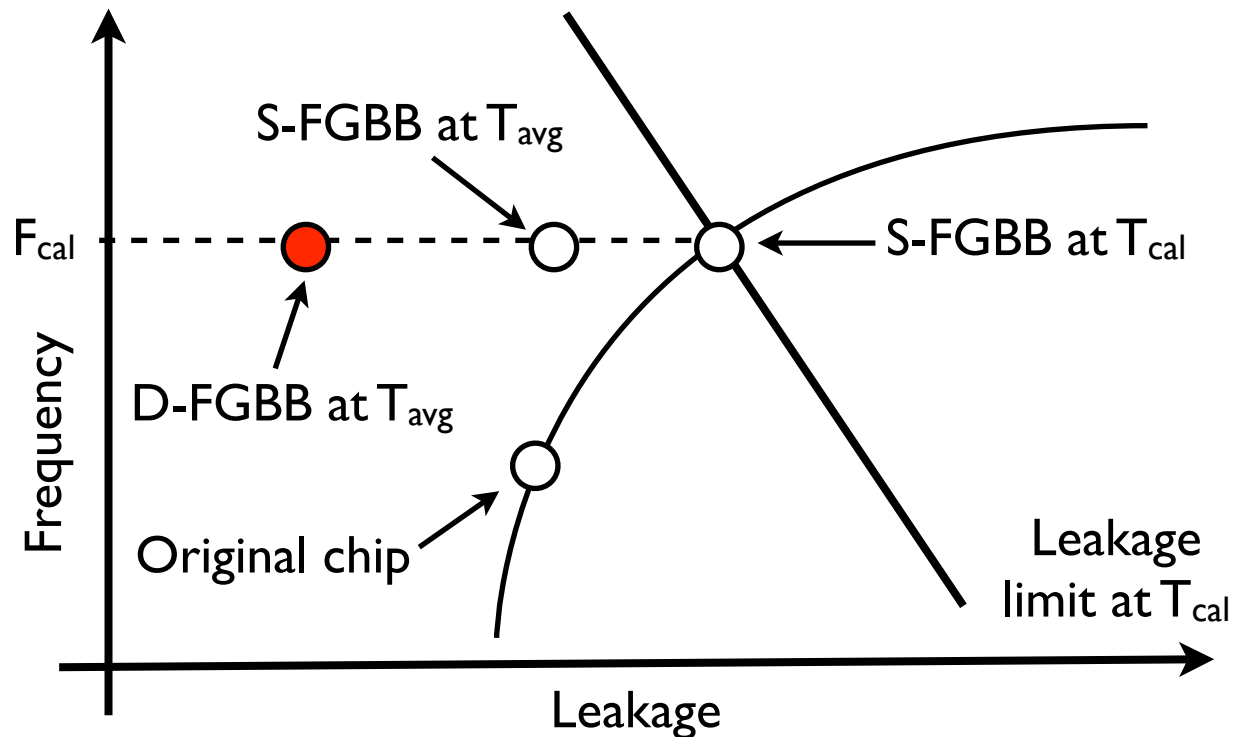
D-FGBB Adapts to Changes in T

- Calibration temperature T_{cal} is conservative
- Average T much lower:



D-FGGB Saves Leakage Power

- S-FGGB finds and sets F_{cal}
- D-FGGB adjusts dynamically to T changes to save power while running at F_{cal}



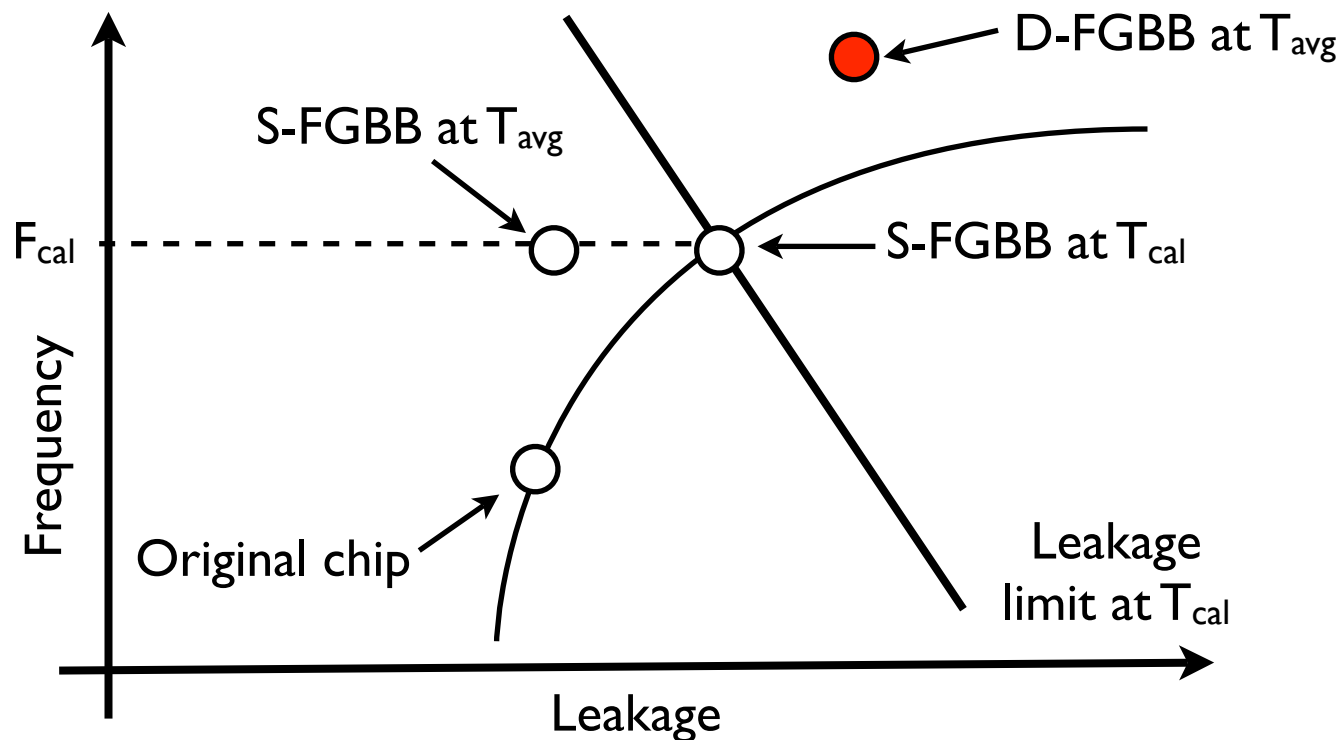
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D-FGGB Improves Performance

- Average power $P_{avg} < P_{max}$
- D-FGGB is used to push the chip to $F_{avg} > F_{cal}$, as long as $P < P_{max}$



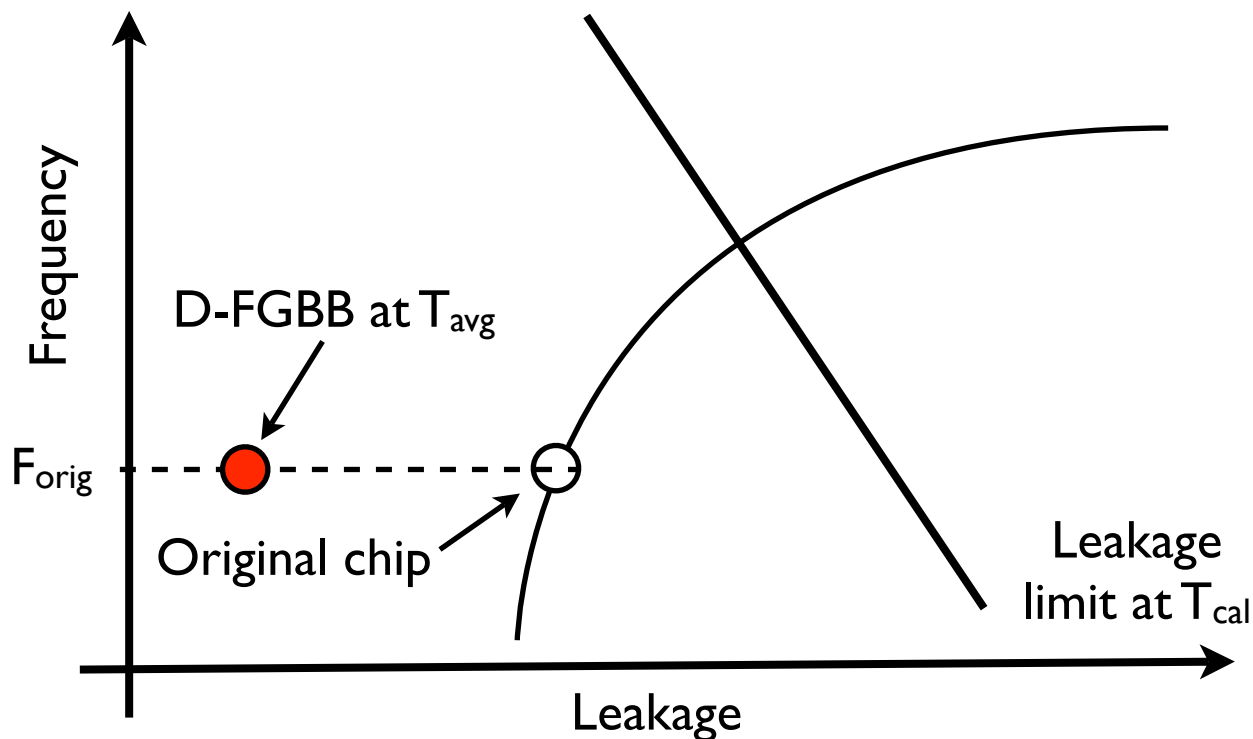
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D-FGGB Saves Leakage Power

- The chip runs at its original F_{orig}
- D-FGGB adjusts dynamically to T changes to save power while running at F_{orig}



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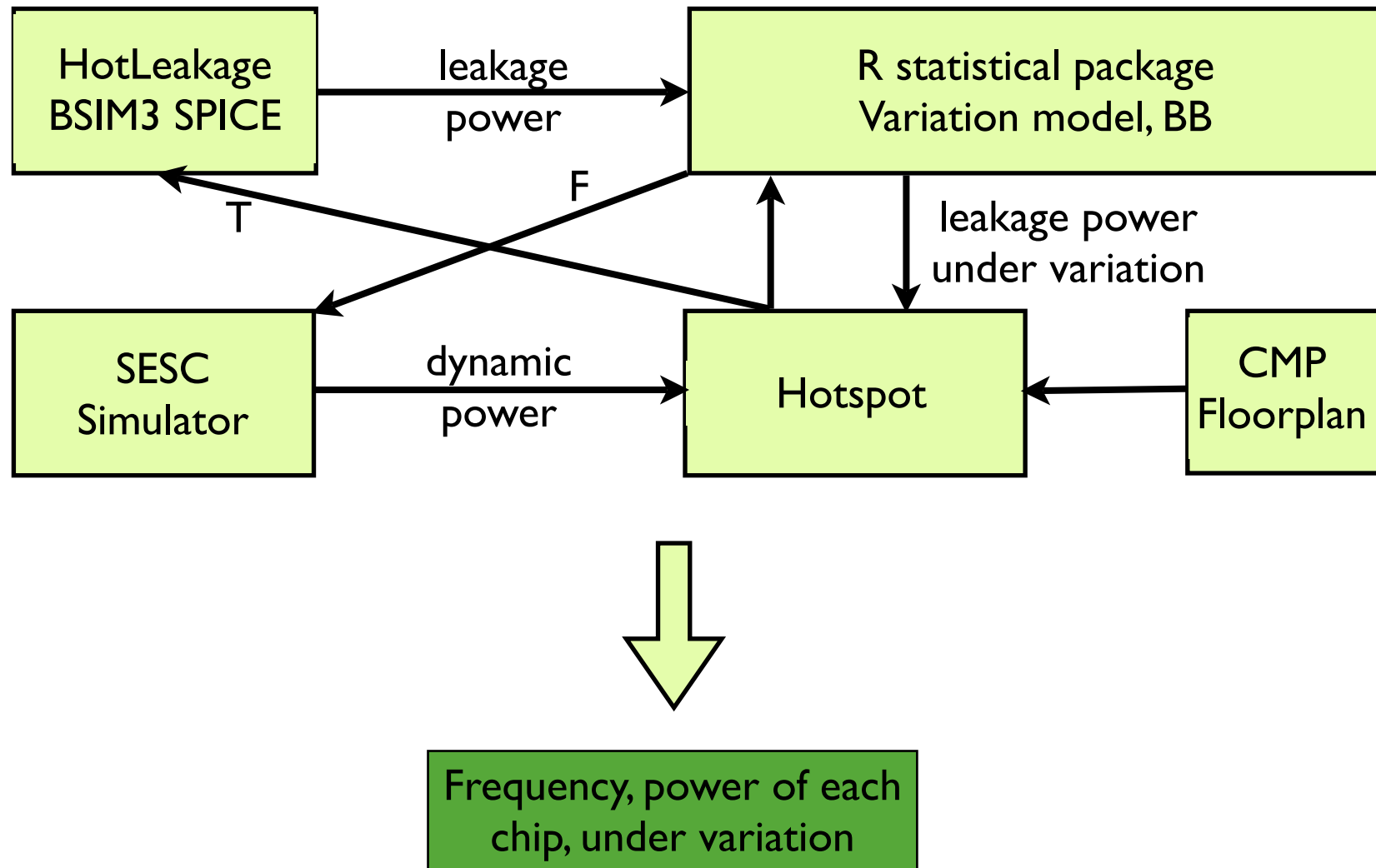


Evaluation Infrastructure

- Statistical package R to generate variation maps for 200 chips
- SESC - cycle accurate microarchitectural simulator - execution time, dynamic power
 - Mix of SPECint and SPECfp benchmarks
- HotLeakage, SPICE model - leakage power
- Hotspot - temperature estimation



Evaluation Infrastructure

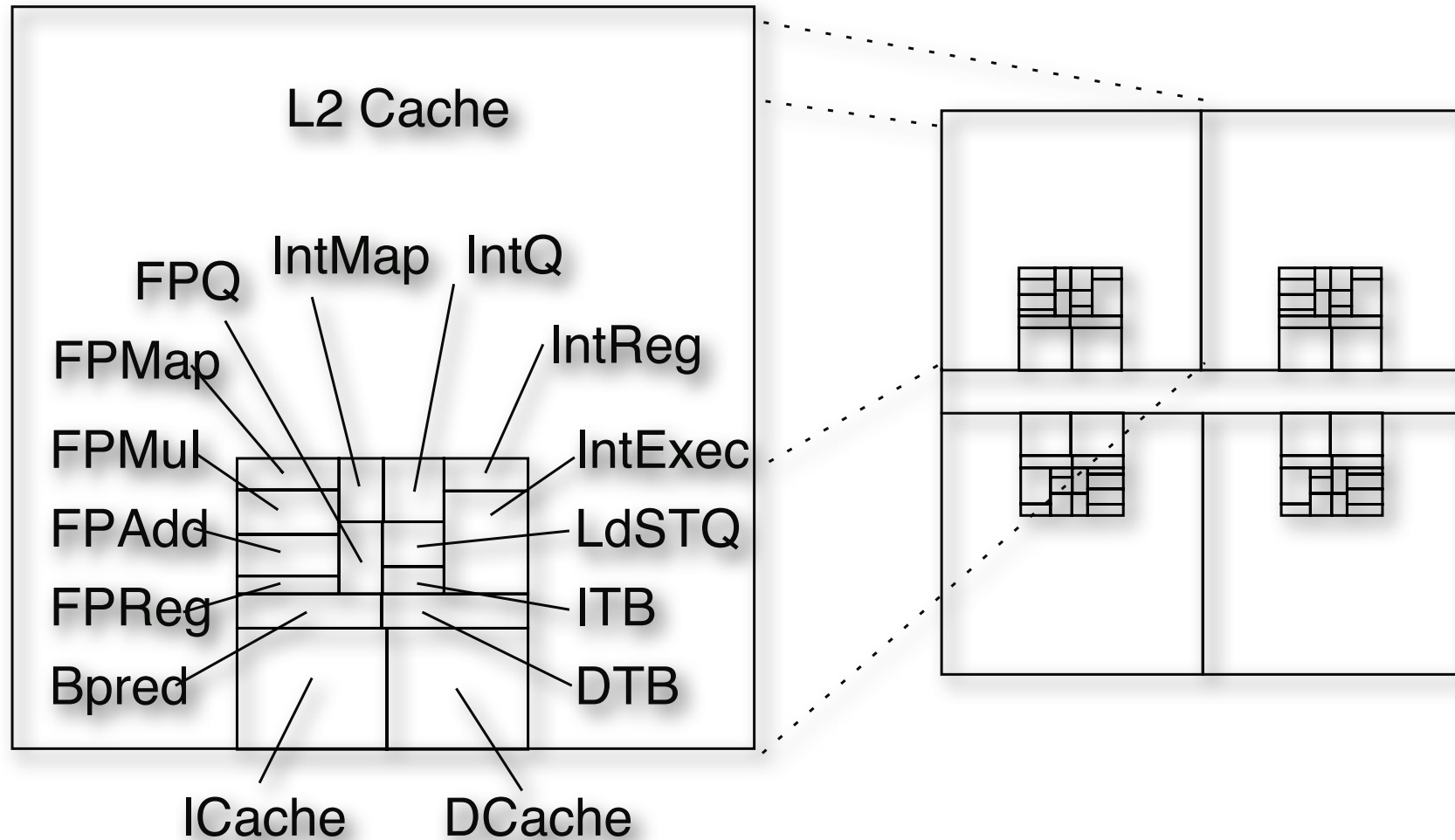


Evaluation Methodology

- 4-core CMP, based on Alpha 21364
- 45nm technology, 4GHz
- V_{th} variation: $\sigma_{V_{th}}/\mu_{V_{th}}=0.3-0.12$, $\sigma_{sys}=\sigma_{rand}$
- L_{eff} variation $\sigma_{L_{eff}}= \sigma_{V_{th}}/2$
- $V_{dd}=1V$, $V_{th0}=150mV$, $V_{bb}= \pm 500mV$

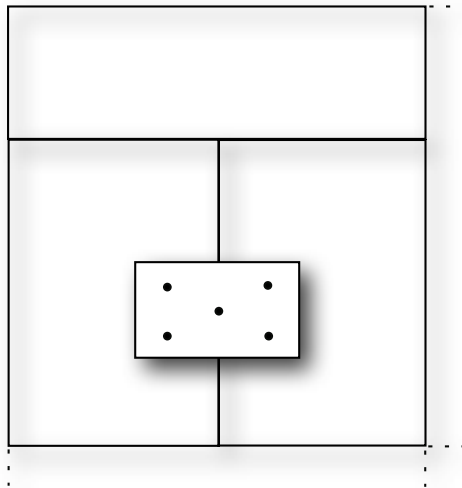


CMP Architecture

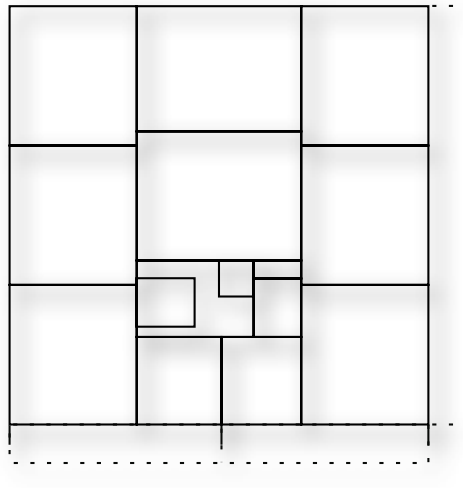


Body Bias Cells

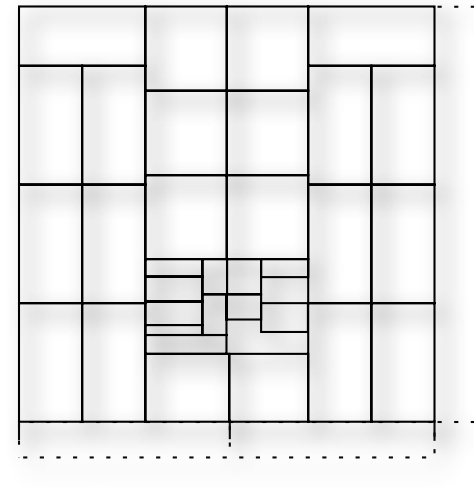
- We partition each core into BB cells
- Shapes and sizes follow functional units



FGBB16

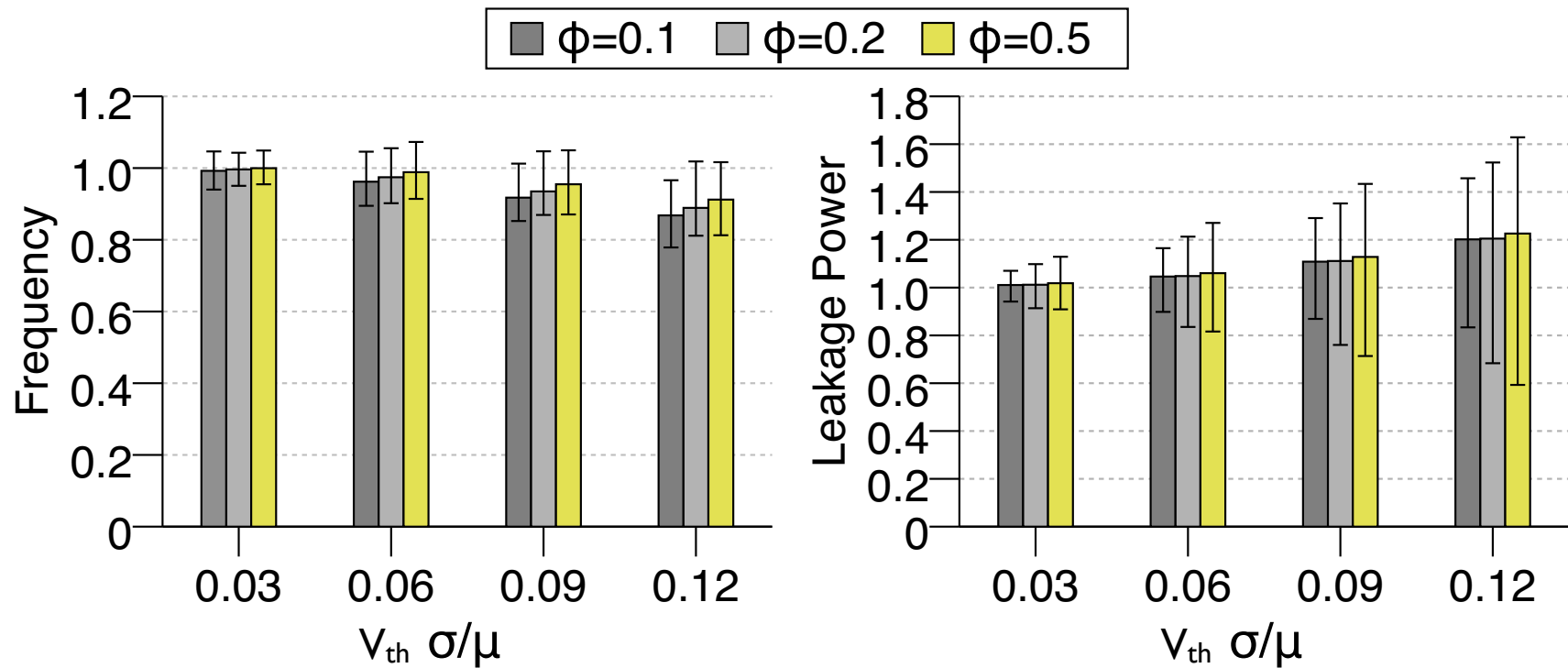


FGBB64



FGBB144

Variation Impact

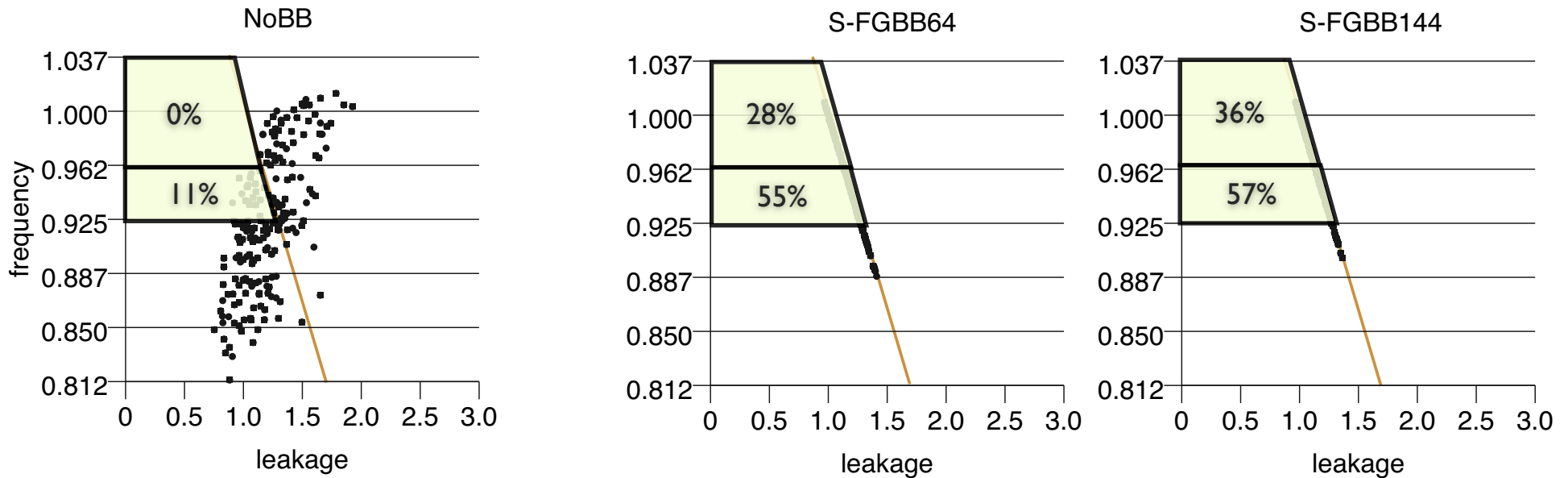


Applications of D-FGGB

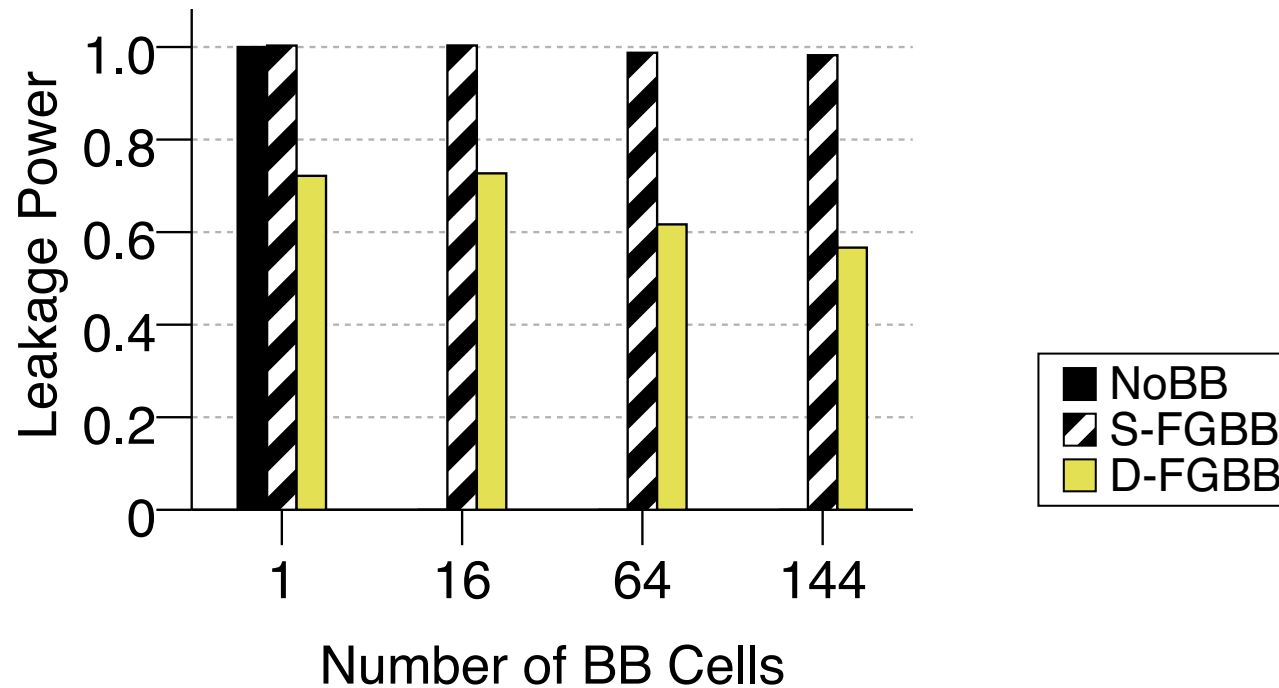
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S-FGGB Improves the Chip's Operating Point



D-FGGB Reduces Leakage



- Large leakage reduction after binning: 28-42%
- More BB cells result in higher savings

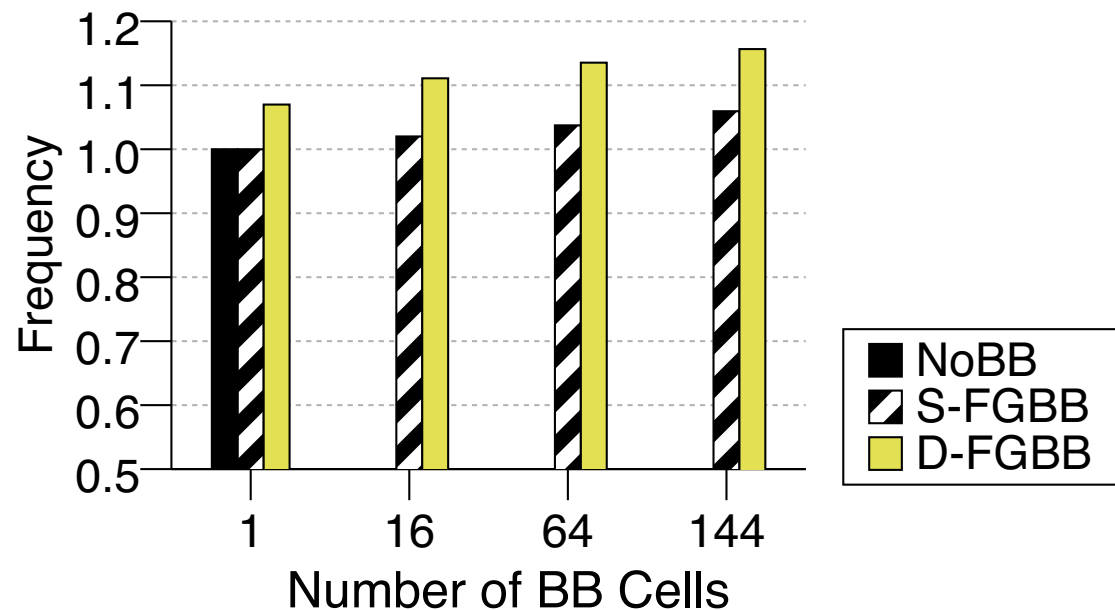


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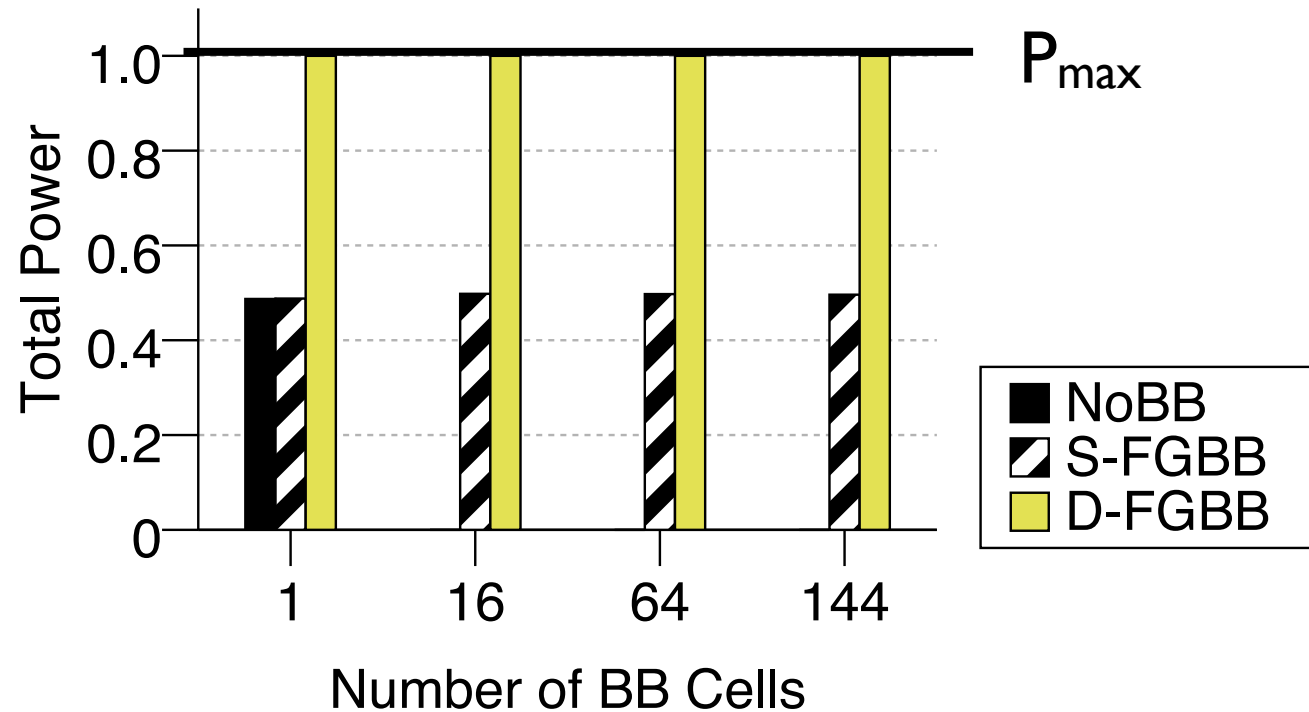
D-FGGB Improves Frequency



- Average frequency improvement 7-9% over S-FGGB and 7-16% over NoBB
- More BB cells result in higher increase



Power Cost



- Significant power cost, but still within the power budget

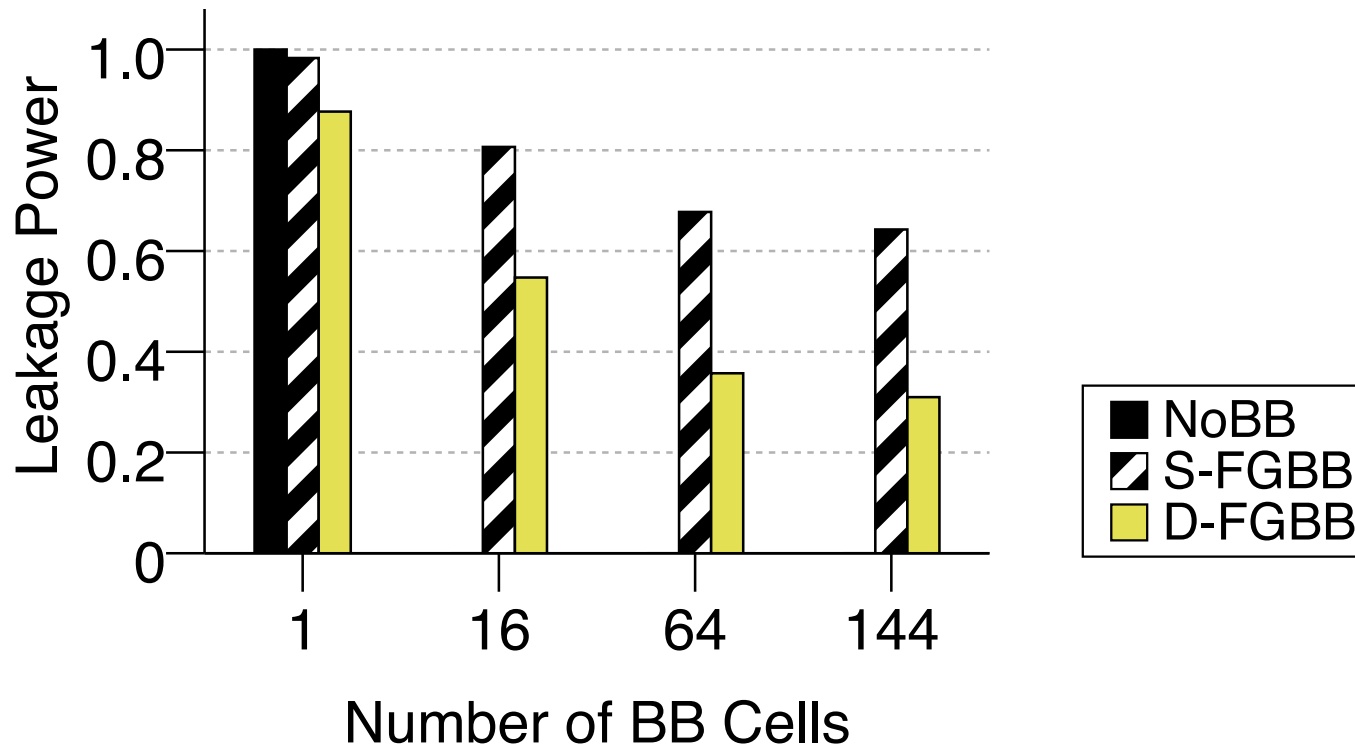


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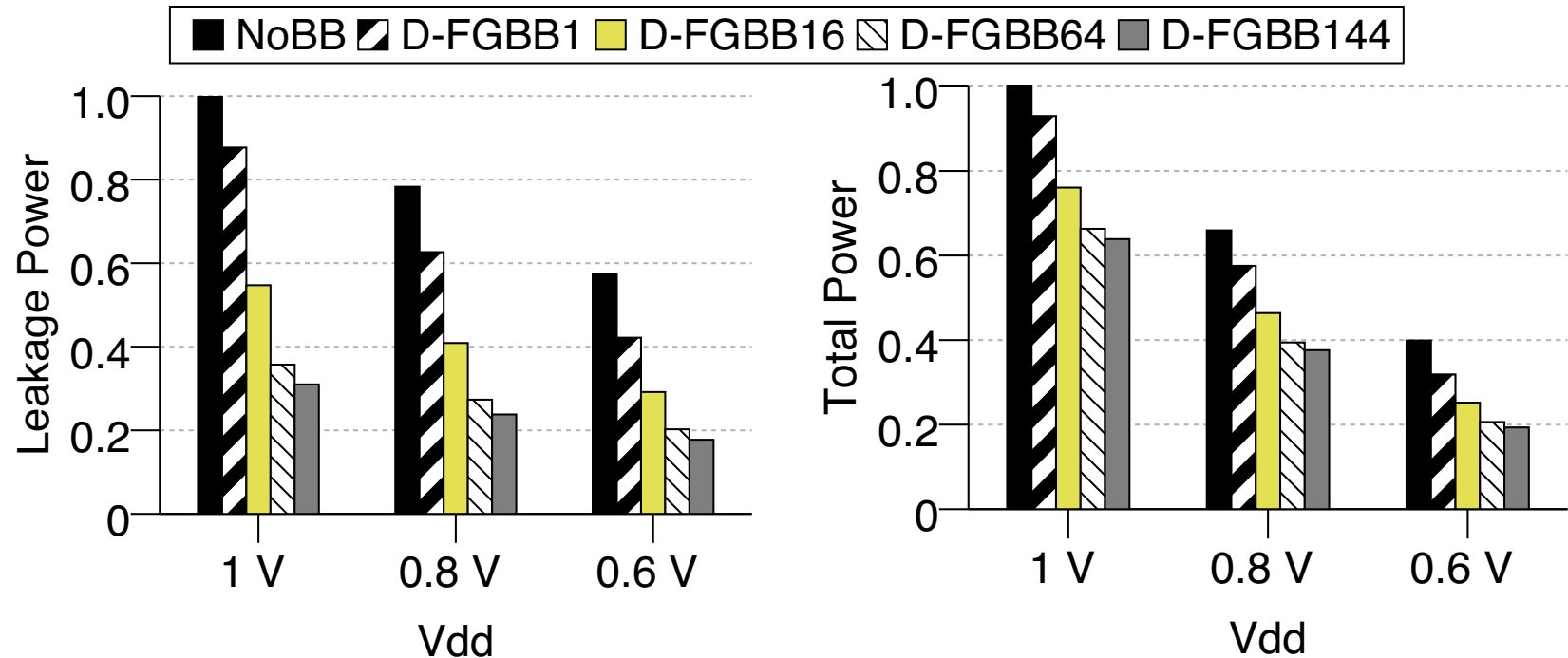
- Large leakage reduction at constant frequency: 10-51% vs. S-FGGB and 12-69% vs NoBB
- More BB cells result in higher savings

Combining D-FGGB with DVFS

- D-FGGB targets leakage power
- DVFS targets mostly dynamic power
- Can they be combined effectively?



Combining D-FGGB with DVFS



- D-FGGB scales well with DVFS
- S-FGGB does not scale unless calibrated at multiple voltages



Conclusions

- D-FGGB is an effective and versatile tool to address parameter variation
- We show three scenarios:
 - Normal: 28-42% leakage savings vs. S-FGGB
 - High performance: 7-9% frequency increase
 - Low power: 10-51% leakage reduction vs. S-FGGB
- Combines well with DVFS



More in our MICRO 2007 paper

<http://iacoma.cs.uiuc.edu>

- More details on the variation model
- A solution for combining D-FGGB with DVS
- Estimated overheads of D-FGGB
- More implementation details

Thank you! Questions?

